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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10038375	FILING DATE 01/04/2002	CLASS 438	SUBCLASS 620 ⁺	GAU 2842	EXAMINER Sarkar
**APPLICANTS: Kim Jae; Lee Sang; 2829					
**CONTINUING DATA VERIFIED:					
** FOREIGN APPLICATIONS VERIFIED: REPUBLIC OF KOREA 2001-36599 06/26/2001					
PG-PUB <input type="checkbox"/> DO NOT PUBLISH <input type="checkbox"/> RESCIND <input type="checkbox"/>					
Foreign priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no 35 USC 119 conditions met <input type="checkbox"/> yes <input type="checkbox"/> no Verified and Acknowledged Examiners's initials				ATTORNEY DOCKET NO 30205/37916	
TITLE : Chemical mechanical polishing slurry and process for ruthenium films					
U.S. DEPT. OF COMM./PAT. & TM.-PTO-436L (Rev. 12-94)					

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	
		Print Claims for O.S.	
ISSUE FEE		DRAWING	
Amount Due	Date Paid	Sheets Drawn	Fig. Drawn
		Print Fig.	
<input type="checkbox"/> TERMINAL DISCLAIMER		Primary Examiner	
		PREPARED FOR ISSUE	
		Application Examiner	
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